

# ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

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|--|--|-------------|------------|---------------|------|-------|----------|
| <b>Title of<br/>Invention</b>  | <b>YIELD IMPROVEMENT IN SILICON-GERMANIUM EPITAXIAL<br/>GROWTH</b> |             |            |               |      |       |          |
| <p>Application Number :<br/>Confirmation Number:<br/>First Named Applicant: Mark Dupuis<br/>Attorney Docket Number: BUR920040106US1<br/>Art Unit:<br/>Examiner:<br/>Search string: ( 5358895 or 20030139000 ),pn</p> |  |             |            |               |      |       |          |
| <b>US Patent Documents</b>   |  |             |            |               |      |       |          |
| <b>Note: Applicant is not required to submit a paper copy of cited US Patent Documents</b>   |  |             |            |               |      |       |          |
| init   | Cite.No.   | Patent No.  | Date       | Patentee      | Kind | Class | Subclass |
| T.D  | 1  | 5358895     | 1994-10-25 | Steele, et al | —    | —     | —        |
| <b>US Published Applications</b>   |  |             |            |               |      |       |          |
| <b>Note: Applicant is not required to submit a paper copy of cited US Published Applications</b>   |  |             |            |               |      |       |          |
| init   | Cite.No.   | Pub. No.    | Date       | Applicant     | Kind | Class | Subclass |
| T.D  | 1  | 20030139000 | 2003-07-24 | Bedell, et al | —    | —     | —        |
| <b>Signature</b>   |  |             |            |               |      |       |          |
| Examiner Name  |  |             |            | Date          |      |       |          |
| T. DANK  |  |             |            | 11/23/04      |      |       |          |